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METHOD AND DEVICE FOR EXPOSURE

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Abstract

PURPOSE:To make accurate transfer possible by exposing photoresist after maintaining the moisture in the photoresist in a uniform state by setting gas such as air to be blown to the photoresist at a prescribed temp. CONSTITUTION:The work (silicon wafer) 3 which is formed with photoresist 2 in a film shape on the surface is installed on an XY table 1 which is movable at a right angle and in parallel. Gas such as air of controlled moisture and temp. is fed to a pneumatically operated focusing device 19, from which it is flowed into the space between an objective lens and the photoresist. Then, this space is filled with the gas of the prescribed humidity and the moisture contained in the photoresist is kept constant. The height and position of an objective lens 5 is determined by the device 19 maintained in such a state, and the surface of the photoresist 2 is exposed, whereby the accurate transfer is made possible.

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